Supporting Information

for

General Synthesis Strategy of ZrO₂ Nanofilms with Few-Atom Layered Thickness for Boosting

Triethylamine Detection†

Jie Lu^a, Xiang Huang^a, Yuanyu Xie^a, Hongjie Liu^{b,*}, Shaopeng Wang^c, Yongchang Chen^a, Liwei Wang^{c,d,e*}

^a School of Life Science and Technology, Guangxi University, Nanning, 530004, PR China

^b School of Chemistry and Chemical Engineering, Guangxi University, Nanning, 530004, PR China

^c School of Marine Sciences, Guangxi University, Nanning, 530004, PR China ^d School of Resources, Environment and Materials, Guangxi Key Laboratory of Processing for Non-ferrous Metallic and Featured Materials, Guangxi University, Nanning, 530004, PR China

^e Southern Marine Science and Engineering Guangdong Laboratory (Zhuhai), Zhuhai, 519080, China

*Corresponding Authors

Emails: hongjieliu2008@163.com (Dr. H.J. Liu) wangliwei@gxu.edu.cn (A/Prof. L.W. Wang)

Experimental

Synthesis of ultrathin ZrO₂NFs

ZrOCl₂·8H₂O (0.50 g), terephthalic acid (0.16 g) and lysine (0.21 g) were dissolved in 30 ml of ethanol. After ultrasonic suspension for 5 min, 5 mL of ethanolamine was added dropwise while stirring. After continuously adding 5 mL of glacial acetic acid, a homogeneous mixture was transferred to a 50 mL stainless steel reactor with a Teflon liner and heated at 120°C for 4 h and then cooled down to room temperature. The resulting product was washed using ethanol by several times followed by centrifugation. The centrifuged product was dried in an oven at 60°C. The product was transferred to a temperature programmed tubular furnace and calcined at 450°C in air atmosphere for 2 h to obtain the final samples.

Synthesis of ultrathin Fe₂O₃ NFs

FeCl₃·6H₂O (0.54 g), terephthalic acid (0.16 g) and lysine (0.21 g) were dissolved in 30 mL of ethanol. After ultrasonic suspension for 5 min, 1 mL of ethanolamine was added dropwise while stirring. After continuously adding 5 mL of glacial acetic acid, a homogeneous mixture was transferred to a 50 mL stainless steel reactor with a Teflon liner and heated at 120°C for 4 h and then cooled down to room temperature. The resulting product was washed using ethanol by several times followed by centrifugation. The centrifuged product was dried in an oven at 60°C. The product was transferred to a temperature programmed tubular furnace and calcined at 450°C in air atmosphere for 3 h to obtain the final samples.

Synthesis of ultrathin NiO NFs

NiCl₂·6H₂O (0.48 g), terephthalic acid (0.24 g) and lysine (0.14 g) were dissolved in 30 mL of ethanol. After ultrasonic suspension for 5 min, 5 mL of ethanolamine was added dropwise while stirring. After continuously adding 5 mL of glacial acetic acid, a homogeneous mixture was transferred to a 50 mL stainless steel reactor with a Teflon liner and heated at 120°C for 4 h and then

cooled down to room temperature. The resulting product was washed using ethanol by several times followed by centrifugation. The centrifuged product was dried in an oven at 60°C. The product was transferred to a temperature programmed tubular furnace and calcined at 450°C in air atmosphere for 3 h to obtain the final samples.

Synthesis of ultrathin Co₃O₄ NFs

CoCl₂·6H₂O (0.48 g), terephthalic acid (0.24 g) and lysine (0.14 g) were dissolved in 30 mL of ethanol. After ultrasonic suspension for 5 min, 5 mL of ethanolamine was added dropwise while stirring. After continuously adding 5 mL of glacial acetic acid, a homogeneous mixture was transferred to a 50 mL stainless steel reactor with a Teflon liner and heated at 120°C for 4 h and then cooled down to room temperature. The resulting product was washed using ethanol by several times followed by centrifugation. The centrifuged product was dried in an oven at 60°C. The product was transferred to a temperature programmed tubular furnace and calcined at 450°C in air atmosphere for 3 h to obtain the final samples.

Synthesis of ultrathin W/ZrO₂NFs

 $ZrOCl_2 \cdot 8H_2O$ (0.48 g), WCl₆ (0.04 g), terephthalic acid (0.16 g) and lysine (0.21 g) were dissolved in 30 ml of ethanol. After ultrasonic suspension for 5 min, 5 mL of ethanolamine was added dropwise while stirring. After continuously adding 5 mL of glacial acetic acid, a homogeneous mixture was transferred to a 50 mL stainless steel reactor with a Teflon liner and heated at 120°C for 4 h and then cooled down to room temperature. The resulting product was washed using ethanol by several times followed by centrifugation. The centrifuged product was dried in an oven at 60°C. The product was transferred to a temperature programmed tubular furnace and calcined at 450°C in air atmosphere for 2 h to obtain the final samples.

Sensors fabrication

First, the prepared sensor material was mixed with deionized water to form a uniform slurry, then coated on the Pd/Ag-based interdigital electrode electrodes

to form a uniform sensor film, which was dried in the air at room temperature. Air was used as the background and dilute gas. Changes in the resistance were recorded when the sensing devices were exposed to a target gas at a certain operating temperature. The sensing response was defined as $S = R_a/R_g$, where R_a was the resistance for sensor exposure to air and R_g was the resistance of the sensor in the presence of the test gas. The response or recovery time was expressed as the time taken for the sensor output to reach 90% of its saturation after applying or switching off the gas in a step function.

Characterizations

The samples were characterized by means of powder X-ray Diffraction analysis (XRD; Rigaku Ultima IV, Cu K α radiation, λ = 1.5418 Å, Japan), Fieldemission Scanning Electron Microscope (FESEM; Hitachi SU5000, Japan), High Resolution Transmission Electron Microscope with Energy Dispersive Spectroscopy (HRTEM/EDS; FEI TeN-Cai G2 f20 s-twin, 200 kV, USA), Atomic Force Microscope (AFM; Hitachi 5100N Japan), X-ray Photoelectron Spectroscopy (XPS; Thermo SCIENTIFIC ESCALAB 250Xi, Al K α X-ray monochromator, USA), Ultraviolet–visible spectroscopy (UV/Vis; PerkinElmer, LAMBDA 1050+, USA), Fourier Transform Infrared Spectroscopy (FTIR; SHIMADZU IRTrace-100, Japan), and Thermogravimetric Analysis (TGA; NETZSCH STA 449 F5, German).

S4

Figure Captions

1. (a) TGA analysis of Zr-based precursor after hydrothermal treatment (the weight loss tends to be stable after annealing at 450°C, and there is no weight loss even up to 600°C.), and (b) FT-IR analysis (the absorption peak at 1545 cm⁻¹ is caused by the asymmetric stretch vibration of COO⁻, and the absorption peak at 1435 cm⁻¹ is caused by the symmetrical stretching vibration of COO⁻).

(Figure S1);

2. SEM images of ZrO_2 NFs annealed at (a) 400°C, (b) 450°C, (c) 500°C, (d) 550°C, and (e) 600°C, respectively. (**Figure S2**);

3. SAED image of ZrO₂ NFs. (Figure S3);

4. (a-e) The SEM of ZrO₂ NFs with the different amounts of Lysine (0.5, 1.0, 1.5, 2.0, and 2.5 mmol). (Figure S4);

5. Ultrathin Fe_2O_3 NFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thickness of Fe_2O_3 is about 8.1 nm), and (e-f) EDS results (Fe and O elements are uniformly distributed). (**Figure S5**);

6. Ultrathin Co_3O_4 NFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thickness of Co_3O_4 is about 3.9 nm), and (e-f) EDS results (Co and O elements are uniformly distributed). (**Figure S6**);

7. Ultrathin NiONFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thicknesses of NiO is about 3.8 nm), and (e-f) EDS results (Ni and O elements are uniformly distributed). (**Figure S7**);

8. Ultrathin W/ZrO₂ NFs: (a) SEM image with two-dimensional structure, (b) XRD pattern, (c) AFM test (the film thickness of W/ZrO₂ NFs is about 3.2 nm), and (d-f) EDS results (W, Zr and O elements are uniformly distributed). (Figure S8);

9. (a) SEM image of ZrO_2 NPs, (b) XRD pattern, the (c) CV and (d) EIS measurements of ZrO_2 NPs were prepared by UIO-66 synthesis strategy. (**Figure S9**);

10. The gas sensing performances of various ZrO₂ NFs obtained by annealing

at 400°C, 450°C and 600°C, respectively to 10 ppm of TEA, at the operating temperature of 300°C (To determine the optimal annealing temperature as 450°C). (**Figure S10**);

11. The gas sensing performances of various ZrO_2 NFs obtained with different amounts of lysine as 0.5, 1.0, 1.5, 2.0, and 2.5 mmol, respectively to 10 ppm of TEA, at the operating temperature of 300°C (To determine the optimal lysine amount as 1.5 mmol). (**Figure S11**);

12. The determination of the optimal operating temperature of ZrO₂ NFs-based gas sensor. (**Figure S12**);

13. The dynamic resistance changes of of ZrO_2 NFs to 50 ppm of TEA gas at the operating temperatures of room temperature, 50°C and 150°C, respectively. (**Figure S13**);

14. The band gap diagram obtained by Tauc Plot of ZrO₂ NFs. (Figure S14);

15. The long-term stability of ZrO_2 NFs-based sensor to 1 ppm of TEA gas within one month. (Figure S15).



Figure S1. (a) TGA analysis of Zr-based precursor after hydrothermal treatment (the weight loss tends to be stable after annealing at 450°C, and there is no weight loss even up to 600°C.), and (b) FT-IR analysis (the absorption peak at 1545 cm⁻¹ is caused by the asymmetric stretch vibration of COO⁻, and the absorption peak at 1435 cm⁻¹ is caused by the symmetrical stretching vibration of COO⁻).



Figure S2. SEM images of ZrO_2 NFs annealed at (a) 400°C, (b) 450°C, (c) 500°C, (d) 550°C, and (e) 600°C, respectively.



Figure S3. SAED image of ZrO₂ NFs.



Figure S4. (a-e) The SEM of ZrO_2 NFs with the different amounts of lysine (0.5, 1.0, 1.5, 2.0, and 2.5 mmol).



Figure S5. Ultrathin Fe_2O_3 NFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thickness of Fe_2O_3 is about 8.1 nm), and (e-f) EDS results (Fe and O elements are uniformly distributed).



Figure S6. Ultrathin Co_3O_4 NFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thickness of Co_3O_4 is about 3.9 nm), and (e-f) EDS results (Co and O elements are uniformly distributed).



Figure S7. Ultrathin NiO NFs: (a) SEM image, (b) XRD pattern, (c-d) AFM test result (the film thicknesses of NiO is about 3.8 nm), and (e-f) EDS results (Ni and O elements are uniformly distributed).



Figure S8. Ultrathin W/ZrO₂ NFs: (a) SEM image with two-dimensional structure, (b) XRD pattern, (c) AFM test (the film thickness of W/ZrO₂ NFs is about 3.2 nm), and (d-f) EDS results (W, Zr and O elements are uniformly distributed).



Figure S9. (a) SEM image of ZrO_2 NPs, (b) XRD pattern, the (c) CV and (d) EIS measurements of ZrO_2 NPs were prepared by UIO-66 synthesis strategy.



Figure S10. The gas sensing performances of various ZrO_2 NFs obtained by annealing at 400°C, 450°C and 600°C, respectively to 10 ppm of TEA, at the operating temperature of 300°C (To determine the optimal annealing temperature as 450°C).



Figure S11. The gas sensing performances of various ZrO_2 NFs obtained with different amounts of lysine as 0.5, 1.0, 1.5, 2.0, and 2.5 mmol, respectively to 10 ppm of TEA, at the operating temperature of 300°C (To determine the optimal lysine amount as 1.5 mmol).



Figure S12. The determination of the optimal operating temperature of ZrO_2 NFs-based gas sensor to 50 ppm of TEA.



Figure S13. The dynamic resistance changes of of ZrO_2 NFs to 50 ppm of TEA gas at the operating temperatures of room temperature, 50°C and 150°C, respectively.



Figure S14. The band gap diagram obtained by Tauc Plot of ZrO_2 NFs.



Figure S15. The long-term stability of ZrO_2 NFs-based sensor to 1 ppm of TEA gas within one month.

| | Binding | Binding energy | nergy Binding energy of | |
|--------------------------------|----------------------|-------------------------|-------------------------------|-----------|
| | energy of | of Zr 3d _{3/2} | O1s | |
| | Zr 3d _{5/2} | | | |
| YSZ | 181.9 eV | 184.3 eV | 529.6 eV | 1 |
| ZrO ₂ nanoparticles | 182 eV | 184.4 eV | 530 eV; 531.5 eV | 2 |
| ZrO ₂ film | 182.6 eV | 185 eV | 530 eV; 532 eV | 3 |
| carbon-doped ZrO ₂ | 182.2 eV | 184.6 eV | 529.7 eV; 530.9 eV; 532 eV | 4 |
| ultrathin ZrO ₂ NFs | 181.3 eV | 183.7 eV | 529 eV; 530.5 eV | This work |

Table S1. Comparison of element binding energy of different ZrO₂ structures.

Reference

- 1 P. Lackner, A. J. Brandt, U. Diebold and M. Schmid, J. Chem. Phys., 2020, 152, 064709.
- 2 F. Bi, X. Zhang, S. Xiang and Y. Wang, J. Colloid Interface Sci., 2020, 573, 11–20.
- H. Zhao, Y. Zhu, F. Li, R. Hao, S. Wang and L. Guo, *Angew. Chemie Int. Ed.*, 2017, 56, 8766–8770.
- 4 A. Dankeaw, G. Poungchan, M. Panapoy and B. Ksapabutr, *Sensors Actuators, B Chem.*, 2017, **242**, 202–214.

| Material | Tem. | Target | Con. | S(tor)/S(iot) | Res/Rec | Ref. |
|--|------|-----------------|-------|------------------------------|---------|-----------|
| | (°C) | Gas | (ppm) | S(lar)/S(Int) _{Max} | (s) | |
| ZrO ₂ F-ZT | RT | Acetone | 500 | 63.5/30.9 | 6.5/215 | 1 |
| Cr-doped ZrO ₂ | 120 | NH_3 | 700 | 48%/* | 68/72 | 2 |
| In ₂ O ₃ /ZrO ₂ | 260 | Acetone | 100 | 60.3/27 | 1/41 | 3 |
| ZrO ₂ thick film | 250 | NH_3 | 400 | 18%/* | 70/70 | 4 |
| Ti-doped ZrO ₂ | 250 | NO_2 | * | 34.5%/* | 16/2 | 5 |
| Ag-Y/ZrO ₂ | 350 | CO ₂ | 1000 | 230.5/110 | 4/22 | 6 |
| In ₂ O ₃ | 180 | TEA | 100 | 175/80 | 15/300 | 7 |
| In ₂ O ₃ microtube | 300 | TEA | 100 | 75/15.3 | 103/117 | 8 |
| MoO ₃ | 275 | TEA | 100 | 27.1/4 | 30/50 | 9 |
| $ZrO_2 NFs$ | 300 | TEA | 50 | 19.1/2.8 | 6/33 | This work |

 Table S2. Comparison of gas sensing performances between other reported

ZrO₂-based and our ZrO₂ NFs gas sensor

* We define the ratio of the response value S (tar) of the target gas to the maximum response S (int) in the interfering gas to show the selectivity of the sensor.

Reference

- 1 A. Dankeaw, G. Poungchan, M. Panapoy and B. Ksapabutr, *Sensors and Actuators B: Chemical*, 2017, **242**, 202–214.
- E. Hemalatha and N. Gopalakrishnan, DOI:10.1007/s12034-021-025851.
- 3 G. Feng, Y. Che, S. Wang, S. Wang, J. Hu, J. Xiao, C. Song and L. Jiang, Sensors and Actuators: B. Chemical, 2022, **367**, 132087.
- 4 E. Hemalatha and N. Gopalakrishnan, *Bulletin of Materials Science*, 2020,
 43, 12.
- 5 A. H. O. Alkhayatt, S. A. Hussain and E. A. Mahdi, *Optik (Stuttg)*, 2018, **159**, 305–314.
- 6 A. v. Borhade, D. R. Tope and J. A. Agashe, *Journal of Materials Science:*

Materials in Electronics, 2018, 29, 7551–7561.

- Q. Zhang, S. Wang, H. Fu, Y. Wang, K. Yu and L. Wang, ACS Omega, 2020, 5, 11466–11472.
- 8 W. Yang, L. Feng, S. He, L. Liu and S. Liu, *ACS Applied Materials* & *Interfaces*, 2018, **10**, 27131–27140.
- W. Jiang, D. Wei, S. Zhang, X. Chuai, P. Sun, F. Liu, Y. Xu, Y. Gao, X.
 Liang and G. Lu, *New Journal of Chemistry*, 2018, 42, 15111–15120.